

ABSTRACT OF THE DISCLOSURE

A shadow mask has a main mask and an auxiliary mask overlapped on the main mask. Electron beam passage apertures formed in the main mask and the auxiliary mask are arranged at given pitches in the direction of a major axis. Each electron beam passage aperture of the auxiliary mask is a communicating hole, which is formed of a smaller hole in that surface of the auxiliary mask which is in contact with the main mask and a larger hole opening in the opposite surface of the auxiliary mask. The smaller and larger holes of each electron beam passage aperture of the auxiliary mask have their respective central axes extending coaxially with each other and substantially at right angles to the surface of the auxiliary mask in the direction of the major axis.